

Characterization of Photo resist: SPR955-1.8

1. Exposed by GCA Stepper(old)

Conditions:

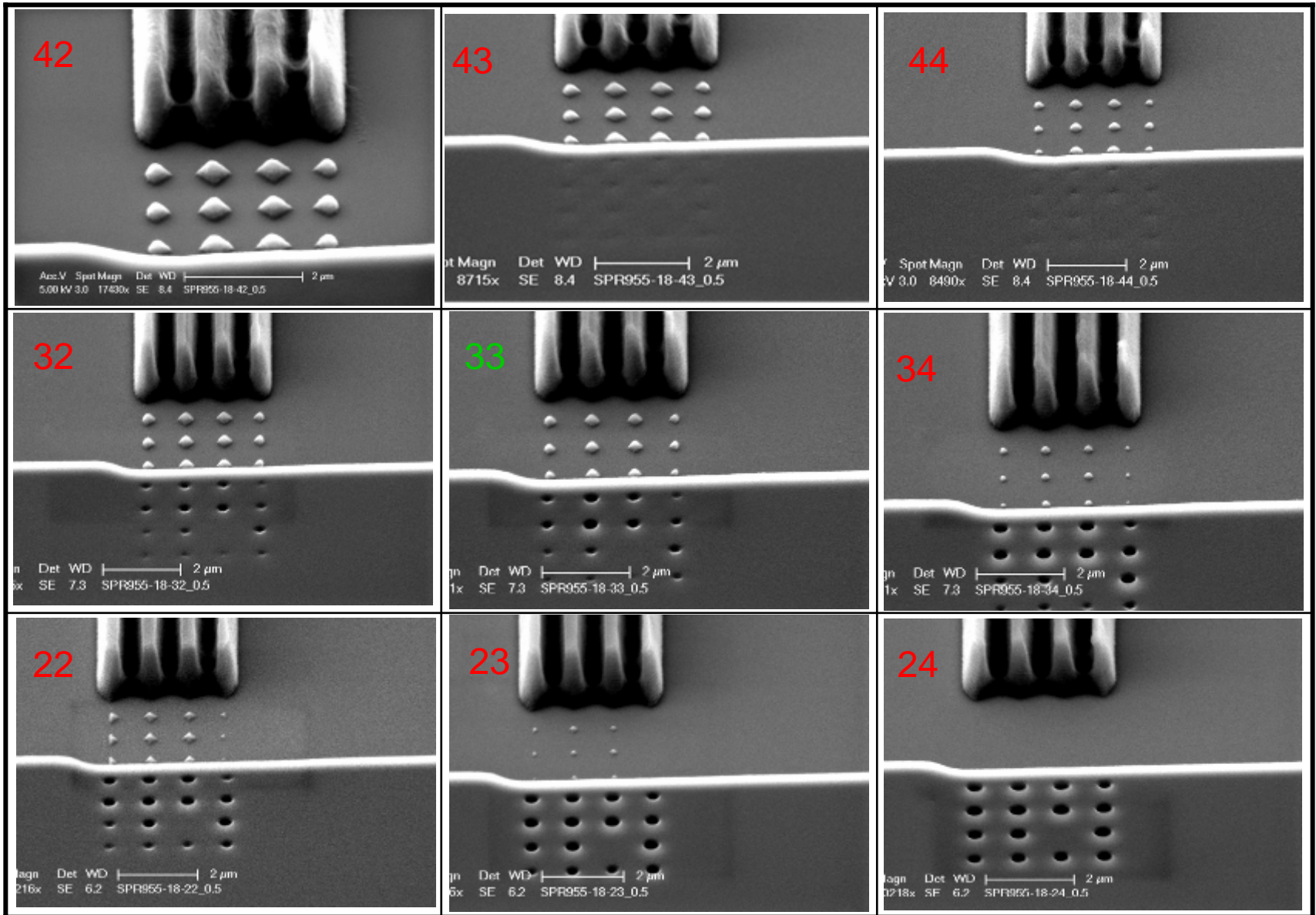
Focus offset: -15 -> 10 (inc:5)
Exposure time: 2.1s -> 2.6s (inc:0.1s)
Coating photo resist: 3000rpm (recipe 5)
Soft bake: 90s@95C
Post bake: 90s@110C

Exposure time →

	2.1s	2.2s	2.3s	2.4s	2.5s	2.6s
-15	61	62	63	64	65	66
-10	51	52	53	54	55	56
-5	41	42	43	44	45	46
0	31	32	33	34	35	36
5	21	22	23	24	25	26
10	11	12	13	14	15	16

1. GCA Stepper(old)

Best exposure results for 0.5 lines



1. GCA Stepper(old)

Best exposure results for 0.7 lines

